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(2-92)

Sheet 1 of 3

Form PTO-1449		Docket Number (Optional) <b>3380.1US (97-842.1)</b>		Application Number <b>Unknown</b>			
INFORMATION DISCLOSURE CITATION IN AN APPLICATION  (Use several sheets if necessary)		Applicant <b>Hill et al.</b>					
		Filing Date <b>February 4, 2002</b>		Group Art Unit <b>2823</b> <b>Unknown</b>			
<b>U.S. PATENT DOCUMENTS</b>							
EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
<i>Lee</i>	4,822,753	04/1989	Pintchovski et al.	<i>438</i>	<i>643</i>		
	4,851,369	07/1989	Ellwanger et al.	<i>438</i>	<i>200</i>		
	4,951,601	08/1990	Maydan et al.	<i>118</i>	<i>179</i>		
	4,975,756	12/1990	Haken, et al.	<i>257</i>	<i>371</i>		
	5,087,593	02/1992	Narula	<i>501</i>	<i>961</i>		
	5,089,438	02/1992	Katz	<i>438</i>	<i>558</i>		
	5,139,825	08/1992	Gordon, et al.	<i>427</i>	<i>255, 2</i>		
	5,192,589	03/1993	Sandhu	<i>427</i>	<i>255, 1</i>		
	5,227,334	07/1993	Sandhu	<i>438</i>	<i>656</i>		
	5,231,056	07/1993	Sandhu	<i>438</i>	<i>654</i>		
	5,240,739	08/1993	Doan, et al.	<i>438</i>	<i>683</i>		
<i>Lee</i>	5,246,881	09/1993	Sandhu, et al.	<i>438</i>	<i>681</i>		
<b>FOREIGN PATENT DOCUMENTS</b>							
	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						YES	NO
<b>OTHER DOCUMENTS</b>						(Including Author, Title, Date, Pertinent Pages, Etc.)	
<i>Lee</i>		Sherman, Arthur: "Growth and Properties of Low Pressure Chemical Vapor Deposited TiN* for Ultra Large Scale Integration" Japanese Journal of Applied Physics, 12/91, Vol. 30, No. 12B.					
<i>Lee</i>		Sandhu, Gurtej S., Meikle, Scott G., Doan, Trung T.: "Metalorganic Chemical Vapor Deposition of TiN Films for Advanced Metallization", American Institute of Physics, 1/18/93.					
<i>Lee</i>		Intemann, A., Koerner, H., Koch, F.: "Film Properties of CVD Titanium Nitride Deposited with Organometallic Precursors at Low Pressure Using Inert Gases, Ammonia, or Remote Activation". The Electrochemical Society, Inc. Vol. 140, No. 11, November, 1993.					
EXAMINER			DATE CONSIDERED				
<i>Aileen Meng Lee</i>			<i>3/5/03</i>				
EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.							

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U.S. PATENT DOCUMENTS						
EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
Lee	5,252,518	10/1993	Sandhu, et al.	438	681	
	5,254,499	10/1993	Sandhu, et al.	438	681	
	5,278,100	01/1994	Doan, et al.	438	681	
	5,344,792	09/1994	Sandhu et al.	438	200	
	5,369,055	11/1994	Chung	438	200	
	5,376,405	12/1994	Doan, et al.	438	680	
	5,399,379	03/1995	Sandhu	427	255.1	
	5,416,045	05/1995	Kauffman, et al.	438	660	
	5,625,231	04/1997	Huang, et al.	257	751	
	5,716,870	02/1998	Foster et al.	438	192	
	5,739,046	04/1998	Lur et al.	438	190	
	Lee	5,801,099	09/1998	Kim et al.	438	666

  

FOREIGN PATENT DOCUMENTS							
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						YES	NO

  

OTHER DOCUMENTS		(Including Author, Title, Date, Pertinent Pages, Etc.)
Lee		Fix, Renaud M., Gordon, Roy G. and Hoffman, David M.: "Synthesis of Thin Films by Atmospheric Pressure Chemical Vapor Deposition Using Amido and Imido Titanium (IV) Compounds as Precursors", Department of Chemistry, Harvard University, Chem Mater. Vol.2 No. 3, 1990, pp.235-241.
Lee		Revesz, A.G., Brown, G.A., Hughes, H.L.: "Bulk Electrical Conduction in the Buried Oxide of SIMOX Structures", The Electrochemical Society, Inc., Vol. 140, No. 11, November 1993.

  

EXAMINER <div style="text-align: center; font-family: cursive;">Kuen Ming Lee</div>	DATE CONSIDERED <div style="text-align: center; font-family: cursive;">3/5/03</div>
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U.S. PATENT DOCUMENTS						
EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
Lee	5,834,356	11/1998	Bothra et al.	438	384	
Lee	5,856,236	01/1999	Lai et al.	438	681	
Lee	5,856,237	01/1999	Ku	438	683	

  

FOREIGN PATENT DOCUMENTS							
	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						YES	NO

  

OTHER DOCUMENTS		(Including Author, Title, Date, Pertinent Pages, Etc.)
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		<div style="font-size: 4em; transform: rotate(-45deg); opacity: 0.5;">/</div>

  

EXAMINER <div style="font-family: cursive; font-size: 1.2em;">Kuan Ming Lee</div>	DATE CONSIDERED <div style="font-family: cursive; font-size: 1.2em;">3/5/03</div>
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